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(54) **MANUFACTURE OF SUBSTRATE FOR OPTICAL
INFORMATION RECORDING MEDIUM**

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(57) Abstract:

PURPOSE: To economically manufacture a substrate by pressing a mold member to the resist film on the surface of the light-transmissive substrate to transfer the rugged pattern and directly etching it.

CONSTITUTION: A photoresist consisting of a novolak resin is applied on a light-transmissive disk-shaped glass substrate 1 to form a resist film 2 having about $5,000\text{\AA}$ thickness. A mold 3 which is provided with an information pattern 4 on one surface and has the same outside diameter as the substrate 1 and consists of nickel is pressed to the film 2 with about 100kg/cm^2 pressure. The mold 3 is peeled from the film 2, and the substrate is etched from the side of the film 2 for about 4.5min by the reactive ion etching method. The film 2 remaining on the substrate 1 is incinerated and removed thereafter, thereby economically and surely obtaining the substrate for optical information recording medium of high quality where information can be recorded with a high density.

